

Watch-Dog Circuit for Quality Guarantee with Subthreshold MOSFET Current

Tetsuya HIROSE^{†a)}, Ryuji YOSHIMURA^{††}, Toru IDO^{††}, Nonmembers, Toshimasa MATSUOKA[†], and Kenji TANIGUCHI[†], Members

SUMMARY We propose an ultra low power watch-dog circuit with the use of MOSFET's operation under subthreshold characteristics. The circuit monitors the amount of the product degradation because the subthreshold current of MOSFET emulates the rate of the general chemical reaction. Its operation was verified with both SPICE simulation and the measurement of the prototype chip. The new circuit embedded in a tag attached to any product could dynamically monitor the degradation regardless of storage conditions.

key words: CMOS, subthreshold current, ultra-low-power, temperature dependence

1. Introduction

We developed a new electronic circuit to monitor the expiration date of consumer products such as medical goods, farm products, foods, beverages, and so on. In general, the expiration date is carefully specified to guarantee their quality before shipping. However, it is not appropriate to fix the expiration date in advance without knowing their preservation conditions. Degradation of any consumer product should be monitored with an ultra-low-power circuit directly attached to the consumer product. The idea of the expiration date checker originates from the fact that the rate of material degradation is expressed with a rate equation regardless of their mechanisms such as chemical reaction and biological proliferation. The circuitry attached to each product can monitor its real quality by emulating the amount of degradation based on the activation energy even if its preservation condition dynamically changes.

2. Overview

Materials are degraded based on the thermal chemical reaction [1]; materials A and B react, and then unwanted material C generates. This reaction is expressed as the following equation.



According to this reaction, a rate equation can be given by

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[†]The authors are with the Department of Electronics and Information Systems, Graduate School of Eng., Osaka University, Suita-shi, 565-0871 Japan.

^{††}The authors are with Texas Instruments Japan Ltd., Tokyo, 160-8366 Japan.

a) E-mail: hirose@eie.eng.osaka-u.ac.jp

$$\frac{d[C]}{dt} = k[A][B] = [A][B]k_0 \exp\left(-\frac{\Delta E_a}{k_B T(t)}\right) \quad (2)$$

where $[A]$ and $[B]$ are the concentrations of the reactants, and $[C]$ is that of the produced unwanted material. The rate constant, k , is given by the pre-exponential factor, k_0 , and the activation energy, ΔE_a for the reaction. k_B is the Boltzmann constant and T the absolute temperature. Integrating the equation from $t = 0$ to $t = t_1$, one can derive the concentration of the unwanted product $[C]$ as

$$[C] = [A]_0[B]_0 k_0 \int_0^{t_1} \exp\left(-\frac{\Delta E_a}{k_B T(t)}\right) dt \quad (3)$$

where the $[A]_0$ and $[B]_0$ are the initial concentrations of the materials, A and B . Among many parameters only temperature ($T(t)$) is a function of time so that the amount of degradation is greatly affected by its thermal history.

2.1 Principle of Circuit Operation

We developed a circuit which emulates the degradation of materials by integrating the subthreshold leakage current of MOSFET whose activation energy is exactly the same as that of the products to be monitored.

Figure 1 shows the measurement result of the $V_{GS}-I_D$ characteristics. The subthreshold drain current of MOSFET is expressed as

$$I_D = I_X \exp\left(\frac{e(V_{GS} - V_X)}{\eta k_B T}\right) \quad (4)$$

where I_X and V_X are temperature-independent but process-dependent parameters, and η the subthreshold slope factor.

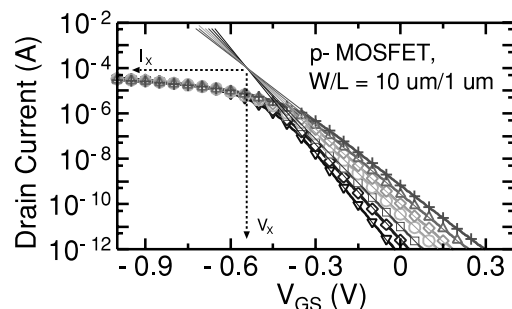


Fig. 1 Measurement results of p-MOSFET $V_{GS}-I_D$ characteristics at different temperatures from -20°C to 100°C . $W/L = 10 \mu\text{m}/1 \mu\text{m}$, $V_{DS} = 100$ mV. V_X and I_X are independent parameter on temperature.

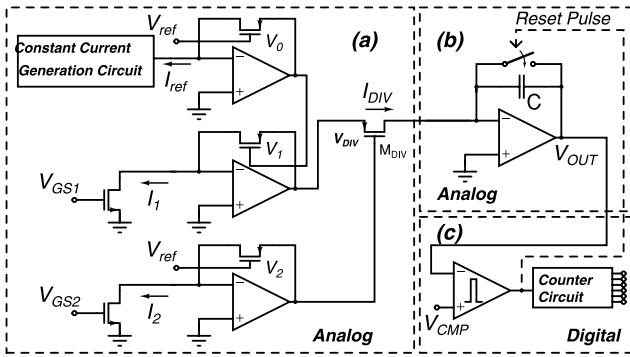


Fig. 2 Block diagram of the circuit. (a) The current divider, (b) the integrator, and (c) the comparator and digital counter circuit.

The ratio of two subthreshold currents, I_{D1} , and I_{D2} can mimic the activation energy as

$$\begin{aligned} \frac{I_{D1}}{I_{D2}} &= \exp\left(-\frac{e(V_{GS,2} - V_{GS,1})}{\eta k_B T}\right) \\ &= \exp\left(-\frac{\Delta E}{k_B T}\right) \end{aligned} \quad (5)$$

$$\Delta E = \frac{e(V_{GS,2} - V_{GS,1})}{\eta} \quad (6)$$

where $V_{GS,1}$ and $V_{GS,2}$ are the input gate-source voltages of the subthreshold currents I_{D1} and I_{D2} , respectively, and ΔE is the emulated activation energy. Integrating the equation with time, one obtains the following equation.

$$\int_0^{t_1} \left(\frac{I_{D1}}{I_{D2}}\right) dt = \int_0^{t_1} \exp\left(-\frac{\Delta E}{k_B T(t)}\right) dt \quad (7)$$

which is proportional to the right-hand side of Eq. (3). At given voltages $V_{GS,1}$ and $V_{GS,2}$, the temperature T is the only variable with time. The degradation rate of the material can be monitored from the integrated value.

In order to achieve high portability, we adopt the use of a button type battery with the nominal voltage of 1.5 V. Figure 2 shows the whole circuitry consisting of the bias circuit, current dividers, integrator, comparator and digital counter. The whole analog elements work at subthreshold region to achieve ultra low power consumption.

2.2 Constant Current Generation Circuit

In the ultra low power circuit, the bias current should be kept constant even in wide temperature change. Figure 3 shows the reference circuit designed. The reference voltage is generated from the four diode connected p-MOSFETs placed in four separate n-wells with their bodies connected to the sources. The circuit generates the reference voltage, V_A , with very little temperature dependence. A p-channel MOS transistor M_{CUR} with a large source resistance biased at the voltage V_A yields the reference current, I_{OUT} , given by

$$I_{OUT} = I_X \exp\left(\frac{e(V_{DD} - I_D R - V_A - V_X)}{\eta k_B T}\right) \quad (8)$$

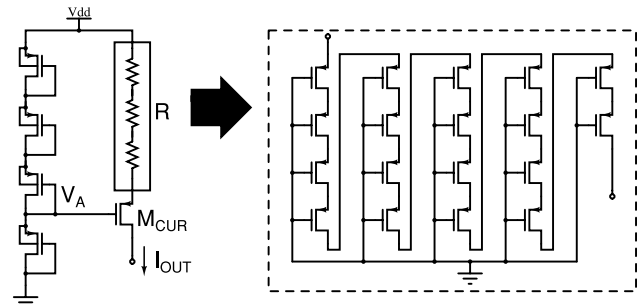


Fig. 3 Constant current generation circuit consisting of four-diode connected p-MOSFETs, a p-MOSFET M_{CUR} , and the 18 p-MOSFETs. Each 18 p-MOSFETs operate in deep triode region.

Table 1 Simulation result of the constant current generation circuit shown in Fig. 3.

Temperature (°C)	-25	0	25	50	75
I_{OUT} (nA)	8.27	8.26	8.26	8.26	8.28

The large resistor degenerates the source-gate voltage V_{SG} ($= V_{DD} - I_D R - V_A$) of the transistor M_{CUR} . As the current increases with temperature, the source-gate voltage V_{SG} decreases, resulting in current suppression, and vice versa. The large resistor consists of 18 p-MOSFETs operating in deep triode region in series connection as shown in Figure 3. The simulation of the bias circuit reveals that the change of the output reference current is suppressed within 1% variation in the temperature range of -25°C to 75°C as shown in Table 1. The power dissipation in operational amplifier biased with this circuit is from 244.4 [nW] to 246.2 [nW] in the temperature range from -25°C to 75°C .

2.3 Elements of the Circuitry

Figure 2(a) shows the subthreshold current divider with logarithm voltage converters consisting of operational amplifiers, feedback transistors, and an anti-log converter transistor [2]. The source-gate voltages of respective feedback transistors, V_0 , V_1 , and V_2 are the function of the current given as

$$V_0 = V_X + \frac{\eta k_B T}{e} \ln\left(\frac{I_0}{I_X}\right) \quad (9)$$

$$V_1 = V_X + \frac{\eta k_B T}{e} \ln\left(\frac{I_1}{I_X}\right) \quad (10)$$

$$V_2 = V_X + \frac{\eta k_B T}{e} \ln\left(\frac{I_2}{I_X}\right) \quad (11)$$

Taking account of the source-gate voltage of a anti-log converter, $V_{SG,DIV} = V_0 + V_1 - V_2$, the output current I_{DIV} is given by

$$\begin{aligned} I_{DIV} &= I_X \exp\left(\frac{e(V_0 + V_1 - V_2 - V_X)}{\eta k_B T}\right) \\ &= I_0 \frac{I_1}{I_2} = I_{ref} \exp\left(\frac{e(V_{GS,1} - V_{GS,2})}{\eta k_B T}\right) \end{aligned}$$

$$= I_{ref} \exp\left(-\frac{\Delta E}{k_B T}\right) \quad (12)$$

which emulates the degradation rate with the activation energy of the products. Note that the current I_{ref} make this circuitry stable. Without the reference current, the output current I_{DIV} sometimes results in too low to be detected, because the transistor's junction leakage current overwhelms the emulated current.

As shown in Fig. 2(b), the capacitor C together with the operational amplifier integrates the current I_{DIV} to generate V_{OUT} given by

$$\begin{aligned} V_{OUT} &= V_{CM} - \frac{1}{C} \int_0^{t_1} I_{DIV} dt \\ &= V_{CM} - \frac{I_{ref}}{C} \int_0^{t_1} \exp\left(-\frac{\Delta E}{k_B T}\right) dt \end{aligned} \quad (13)$$

A long time current integration demands the use of a large capacitor, resulting in a large chip size. This can be, however, avoided by introducing iterative integration technique with a small size capacitor. Once the output voltage V_{OUT} surpasses the comparator's reference voltage V_{CMP} , the comparator generates a reset pulse to discharge the capacitor so that the total number of the reset pulses is effectively equal to a long time integration of the current.

The system repeating above operations provides the information on the degree of degraded products.

Since the prefactor of Eq. (3) ($[A]_0$, $[B]_0$, and k_0) and those of Eq. (13) (I_{ref} , and C) are constant when the target materials are specified, the proportionality factor ($[A]_0[B]_0k_0/I_{ref}/C$) can be fixed before shipping, that is, the allowable maximum number of reset pulses can be preset. The counter circuit monitoring the reset pulses consists of D flip flop (DFF) circuits with small occupation area. In the case of materials with small activation energy, the number of the DFFs has to be increased because the allowable maximum number of reset pulses increases for the materials.

2.4 Simulation Results

Figure 4 shows the simulated output voltage of the integrator at different temperatures from 0°C to 75°C. At a given temperature, the output voltage, the integration of the emulated current, linearly decreases with operation period and the slope of the output voltage increase with the operation temperature, both of which are the natural consequences of its operation principle.

Equation (13) suggests that the slope of the output voltage with time can be expressed as

$$\left|\frac{dV_{OUT}}{dt}\right| = \frac{I_{ref}}{C} \exp\left(-\frac{\Delta E}{k_B T}\right) \quad (14)$$

Eq. (14) indicates that the slope, dV_{OUT}/dt is a linear function of $1/T$ in a semi-log plot. This can be shown in Fig. 5 for the cases of different activation energies ΔE , representing Arrhenius-type relationship.

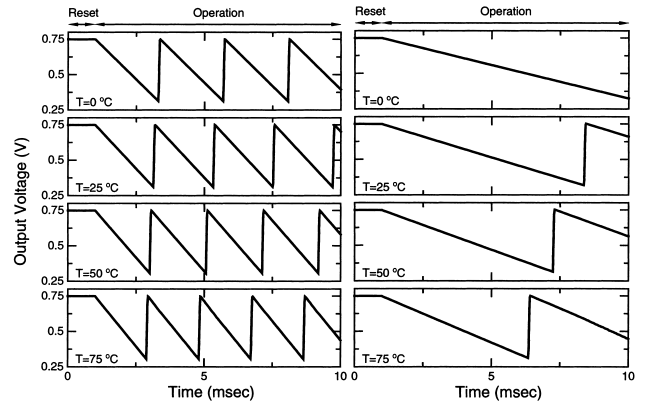


Fig. 4 Simulated output voltage of the integrator at the different temperatures from $T = 0^\circ\text{C}$ to $T = 75^\circ\text{C}$. The left of $V_{GS2} - V_{GS1}$ is set at 50 mV, and the right 100 mV.

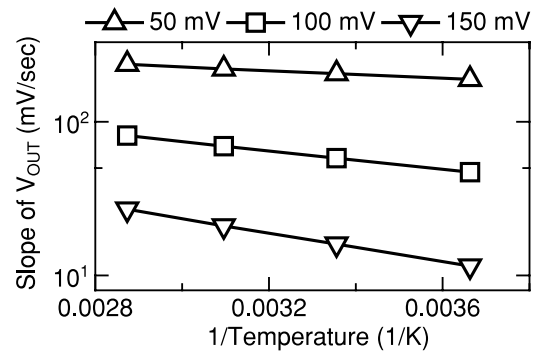


Fig. 5 The slope of the output voltage of the integrator for different $V_{GS,2} - V_{GS,1}$ from 50 mV to 150 mV. The horizontal axis shows the reciprocal of temperature, and the vertical axis shows the slope of the output voltage. According to the Eq. (13), the output voltage of the integrator is on the straight line with the reciprocal of temperature.

Table 2 Performance summary.

Process	0.25 μm 1-poly 5-metal CMOS
V_{DD}	1.5 V
Power	1.37 μW ($T = 75^\circ\text{C}$)
Chip Area	510 (μm) \times 425 (μm)

The system performance is summarized in Table 2. The simulated power consumption of the circuit is only 1.37 μW at 75°C. A button type battery with 35 mAh ensures that the circuit works for 35 mAh/0.91 μA —4.4 year operation.

3. Circuit Implementation

The circuit configuration described in Fig. 2 is difficult to emulate large activation energy because of the reference subthreshold current I_{ref} being very small value. In order to deal with large activation energy, we implemented the circuit as shown in Fig. 6. A MOSFET generate a I_0 current instead of constant current generation circuit. In this circuit, the output current I_{DIV} is given by

$$I_{DIV} = I_0 \frac{I_1}{I_2}$$

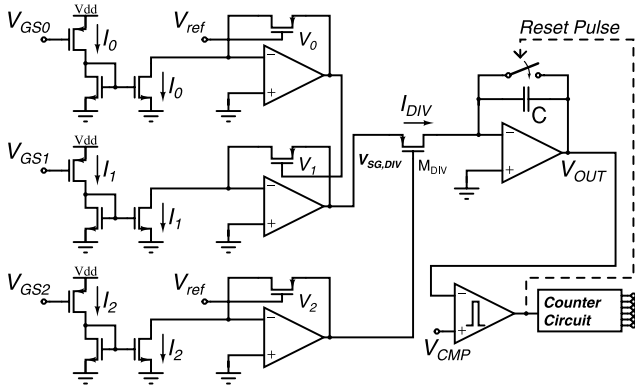


Fig. 6 Implemented circuit. In order to deal with wide range activation energy, input current I_0 is made by a MOSFET instead of reference current I_{ref} .

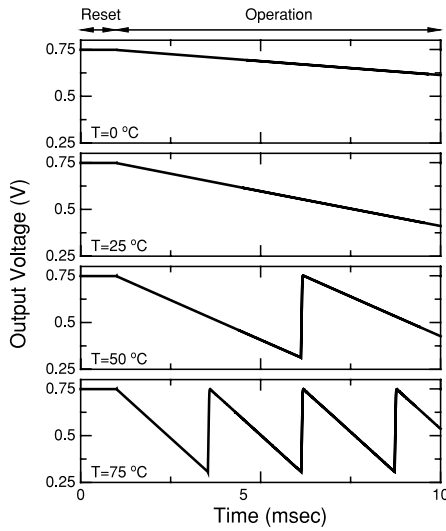


Fig. 7 Simulated output voltage of the integrator at the different temperatures from $T = 0^\circ\text{C}$ to $T = 75^\circ\text{C}$.

$$\begin{aligned}
 &= I_X \exp\left(\frac{e(V_{GS,0} + V_{GS,1} - V_{GS,2} - V_X)}{\eta k_B T}\right) \\
 &= I_X \exp\left(-\frac{\Delta E}{k_B T}\right).
 \end{aligned} \tag{15}$$

As temperature independent I_X is very large value as shown in Fig. 1, the circuit shown in Fig. 6 can emulate large activation energy of ΔE .

Figure 7 shows the simulated output voltage of the integrator. In this simulation, subthreshold slope factor η is 1.3, and $V_{GS,0}$, $V_{GS,1}$, and $V_{GS,2}$ are set at 400 mV, 450 mV, and 500 mV respectively, and $V_X (=750 \text{ mV})$ is extracted from the simulation results, that is, the emulated activation energy is 307 mV. We can figure out that the emulated current of the integrated value is widely change with the operation temperature due to large activation energy.

3.1 Layout and Measurement Results

We designed the prototype chip of the watch-dog circuit

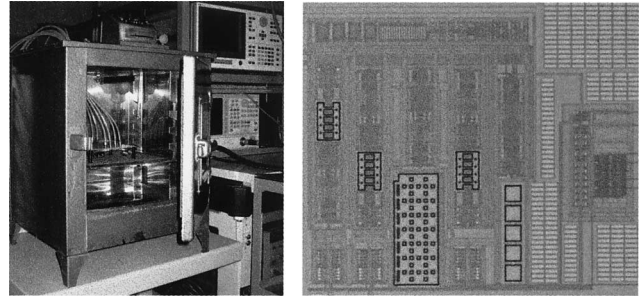


Fig. 8 Left: measurement setup. Right: chip microphotograph.

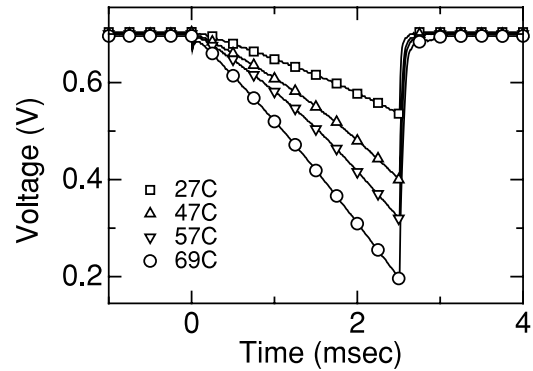


Fig. 9 Measurement results of output voltage of the integrator in temperature range of 27–69°C.

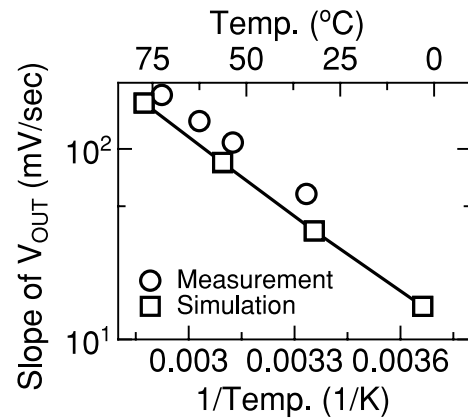


Fig. 10 The slope of the simulated and measured output voltage of the integrator. The output voltage of the integrator are on the straight line with the reciprocal of temperature.

with $0.25 \mu\text{m}$ single-poly and 5-metal CMOS process. The left of Fig. 8 shows the measurement setup including a DC bias generator, thermostatic chamber, and oscilloscope. The right is the photomicrograph of the chip whose layout areas is $510 \mu\text{m} \times 425 \mu\text{m}$. Figure 9 shows the results of the integrator measured in the temperature range from 27°C to 69°C . In the measurement, $V_{GS,0}$, $V_{GS,1}$ and $V_{GS,2}$ are set at 400 mV, 450 mV, and 500 mV respectively. The slope increases with temperatures as expected. These results are consistent well with the SPICE simulation as shown in Fig. 7. Figure 10 shows the slope of the simulated and mea-

sured output voltage. This figure shows that both of them are on the straight line, and the same slope with the reciprocal of the temperature, representing Arrhenius-type relationship.

In this paper, we applied the input bias voltages ($V_{GS,0}$, $V_{GS,1}$, and $V_{GS,2}$) externally. However, in practical application, these voltages can be generated internally from a multiple diode-connected transistor string with three taps.

4. Conclusion

We proposed a watch-dog circuit for the product quality guarantee which dynamically monitors the subthreshold current of MOSFET. Its operation principle is verified with both SPICE simulation and measurement of the prototype chip designed with a $0.25\ \mu\text{m}$ single-poly and 5-metal CMOS process. The new circuitry could be implemented in a tag chip to monitor the degree of degradation for each product upon sale.

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Tetsuya Hirose was born in Tottori, Japan in 1976. He received his M.S., B.S. degrees from Osaka University, Osaka, Japan in 2000 and 2002, respectively. He is now working towards his Ph.D. degree in Osaka University. His current research interests is Analog Circuits.



Ryuji Yoshimura was born in Nara, Japan in 1973. He received his M.S., B.S. and Ph.D. degrees from Osaka University, Osaka, Japan in 1996, 1998 and 2004, respectively. He is now working at Texas Instruments Japan Ltd. His current research interests is Analog Circuits.



Toru Ido was born in Oita, Japan in 1975. He received his M.S., B.S. and Ph.D. degrees from Osaka University, Osaka, Japan in 1998, 2000 and 2003, respectively. He is now working at Texas Instruments Japan Ltd. His current research interests is Analog Circuits.



Toshimasa Matsuoka received the B.S., M.S. and Ph.D. degrees in electronic engineering from Osaka University, Osaka, Japan, in 1989, 1991 and 1996, respectively. During 1991–1998, he worked for the Central Research Laboratories, Sharp Corporation, Nara, Japan, where he was engaged in the research and development of deep submicron CMOS devices and ultra thin gate oxides. Presently, he is an Associate Professor of Electronics Engineering at Osaka University. His current research includes CMOS RF circuits and analog circuits. Dr. Matsuoka is a member of the Japan Society of Applied Physics and the IEEE.



Kenji Taniguchi received the B.S., M.S. and Ph.D. degrees from Osaka University, Osaka, Japan, in 1971, 1973 and 1986, respectively. From 1973 to 1986, he worked for Toshiba Research and Development Center, Kawasaki, Japan where he was engaged in process modeling and the design of MOS LSI fabrication technology. He was Visiting Scientist at Massachusetts Institute of Technology, Cambridge, from July 1982 to November 1983. Presently, he is a Professor of Electronics Engineering at Osaka University. His current research interests are in analog circuits, radio frequency circuits, device physics and process technology. Prof. Taniguchi is a member of the Japan Society of Applied Physics. He is a fellow of the IEEE.